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Notice of Allowability	Application No.	Applicant(s)	
	10/618,650	KONDOH, HIROSHI	
	Examiner	Art Unit	
	Long K. Tran	2818	
The MAILING DATE of this communication appeal all claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R	OR REMAINS) CLOSED in this app or other appropriate communication IGHTS. This application is subject to	plication.  If not includ will be mailed in due	ed course. <b>THIS</b>
1. $\boxtimes$ This communication is responsive to <u>04/03/2006</u> .			
2. $\boxtimes$ The allowed claim(s) is/are <u>1, 2, 3, 5 – 7, 18, 21 – 26 and 3</u>	<u> 29 – 45</u> .		
<ul> <li>3.  Acknowledgment is made of a claim for foreign priority una)  All b)  Some* c)  None of the:</li> <li>1.  Certified copies of the priority documents have</li> <li>2.  Certified copies of the priority documents have</li> <li>3.  Copies of the certified copies of the priority do</li> </ul>	e been received. e been received in Application No		ation from the
International Bureau (PCT Rule 17.2(a)).			
* Certified copies not received:  Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONN THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	of this communication to file a reply MENT of this application.	complying with the re	equirements
4. A SUBSTITUTE OATH OR DECLARATION must be subminformal patent application (PTO-152) which give	res reason(s) why the oath or declara	d'S AMENDMENT or lation is deficient.	NOTICE OF
5. CORRECTED DRAWINGS (as "replacement sheets") must be submitted.			
(a) ☐ including changes required by the Notice of Draftsperson's Patent Drawing Review ( PTO-948) attached			
1)  hereto or 2)  to Paper No./Mail Date			
(b) ☐ including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date			
Identifying indicia such as the application number (see 37 CFR each sheet. Replacement sheet(s) should be labeled as such in	1.84(c)) should be written on the drawi the header according to 37 CFR 1.121	ings in the front (not tr (d).	е раск) от
<ol> <li>DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.</li> </ol>			
Attachment(s)  1. Notice of References Cited (PTO-892)	5. ☐ Notice of Informal I	Patent Application (P	ΓΟ-152)
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6. ☐ Interview Summary Paper No./Mail Da		
3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SB/Paper No./Mail Date 2/27/06,3/28/06		Iment/Comment	
Examiner's Comment Regarding Requirement for Deposit of Biological Material	8. 🛛 Examiner's Statem	nent of Reasons for Al	lowance
	9. 🗌 Other		
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## Response to Amendment

1. This office action is in response to Amendment filed on 04/03/2006.

- 2. Claims 4, 8 17, 19 20, 27, 28 and 46 have been cancelled.
- 3. Claims 1, 24 and 25 have been amended.
- 4. Claims 1, 2, 5 7, 18, 21 26 and 29 45 are presented for examination.

## Information Disclosure Statement

5. This office acknowledges of the following items from the Applicant:

Information Disclosure Statement (IDS) filed on 02/27/2006 and 03/28/2006.

The references cited on the PTO -1449 form have been considered.

#### **EXAMINER'S AMENDMENT**

6. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Mr. Nikolaus P. Schibli on June 12, 2006.

The application has been amended as follows:

#### Claims:

Claim 1 (Currently Amended): A semiconductor device, comprising'.

a gate electrode;

an insulating layer on the gate electrode;

a first electrode on the insulating layer;

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a second electrode on the insulating layer at an interval with the first electrode; an organic semiconductor layer disposed in the interval between the first electrode and the second electrode, [and] covering and contacting at least part of the first electrode and the second electrode; end

a first resistance layer formed on the organic semiconductor layer and having an electrical resistance lower than an electrical resistance of the organic semiconductor layer; and

a second resistance layer formed at least at one of the position between the first resistance layer and the organic semiconductor layers the position between the first electrode and the organic semiconductor layer, and the position between the second electrode and the organic semiconductor layer,

wherein the first resistance layer is formed from a metal selected from the group consisting of chromium (Cr), tantalum (Ta), titanium (Ti), copper (Cu), aluminum (Al), molybdenum (Mo), tungsten (W), nickel (Ni), gold (Au), palladium (Pd), platinum (Pt), silver (Ag), or tin (Sn), and

wherein the second resistance laver has an electrical resistance so that carriers in the organic semiconductor layer am allowed to tunnel through the second resistance laver when a voltage of a predetermined value or more than the predetermined value is applied across the second resistance laver.

Claim 3 (Amended): A semiconductor device, comprising:

a gate electrode;

an insulating layer on the gate electrode;

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a first electrode on the insulating layer;

a second electrode on the insulating layer at an interval with the first electrode;

an organic semiconductor layer disposed in the interval between the first electrode and the second electrode, [and] covering and contacting at least part of the first electrode and the second electrode; and

a first resistance layer formed on the organic semiconductor layer and having an electrical resistance lower than an electrical resistance of the organic semiconductor layer,

wherein one of the first electrode and the second electrode is in contact with the first resistance layer.

Claim 29 (Amended): A liquid crystal display device, comprising a semiconductor device including:

a gate electrode;

an insulating layer on the gate electrode;

a first electrode on the insulating layer;

a second electrode on the insulating layer at an interval with the first electrode;

an organic semiconductor layer disposed in the interval between the first electrode and the second electrode, [and] covering and contacting at least part of the first electrode and the second electrode; and

a first resistance layer formed on the organic semiconductor layer and having an electrical resistance lower than an electrical resistance of the organic semiconductor layer,

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wherein one of the first electrode and the second electrode is in contact with the first resistance layer.

Claim 30 (Amended): A calculating device, comprising at least one of a NOT circuit, a NAND circuit, and a NOR circuit each including a plurality of semiconductor devices,

each of the semiconductor devices including:

a gate electrode;

an insulating layer on the gate electrode;

a first electrode on the insulating layer;

a second electrode on the insulating layer at an interval with the first electrode;

an organic semiconductor layer disposed in the interval between the first electrode and the second electrode, [and] covering and contacting at least part of the first electrode and the second electrode; and

a first resistance layer formed on the organic semiconductor layer and having an electrical resistance lower than an electrical resistance of the organic semiconductor layer,

wherein one of the first electrode and the second electrode is in contact with the first resistance layer

# Allowable Subject Matter

- 7. Claims 1, 2, 5 7, 18, 21 26 and 29 45 are allowed.
- 8. The following is an examiner's statement of reasons for allowance: Claims 1, 2, 5
- -7, 18, 21 -26 and 29 -45 are allowable over the prior art of record because none of

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the prior art whether taken singularly or in combination, especially when these limitations are considered within the specific combination claimed, to teach:

An organic semiconductor layer disposed in the interval between a first electrode and a second electrode and covering at least part of the first electrode and the second electrode, and a first resistance layer being contacted with one of the first electrode and the second electrode as cited in the independent claims 1, 3, 29 and 30; a second resistance layer being formed at least one of the position between the first resistance layer and the organic semiconductor layer, the position between the first electrode and the organic semiconductor layer, and position between second electrode and the organic semiconductor layer and carriers in the organic semiconductor layer allowed to tunnel through the second resistance layer when a voltage equal or more than a voltage of predetermined value being applied across the second resistance layer as cited in the independent claim 1; and among other limitations as cited in the independent claims 1, 3, 29 and 30.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

## Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Long K. Tran whose telephone number is 571-272-1797. The examiner can normally be reached on Mon-Thu.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, MinSun Harvey or Matthew Smith can be reached on 571-272-1835 or 571-272-1907 (Smith). The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

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June 12, 2006